

Optical Configuration (along the light path)

Double-Rotating Compensator Ellipsometer:

Source – Polarizer – Rotating Compensator – Sample – Rotating Compensator – Polarizer – Spectrometer

Spectral Range

Model X: 210nm to 1000nm, 790 wavelengths Model D: 190nm to 1000nm, 800 wavelengths NIR extension: 1000nm to 1690nm, 275 wavelengths

Spectral (Pixel) Resolution/Bandwidth

Model X, D: 1 nm wavelength spacing, 3nm bandwidth NIR extension: 2.5 nm wavelength spacing, 5nm bandwidth

Data Acquisition Rate

Complete acquisition cycle for SE or full MM data is 0.3 seconds. For best signal-to-noise, measurements are averaged from 2-10 seconds at each angle.

Beam Divergence

Less than 0.4°

Beam Diameter

Standard beam is collimated with 3-4mm diameter.

With Focusing, two options are available:

40mm focal length lens:

Beam diameter (short direction) is less than 300 microns.

Maximum Angle of incidence is 75°

27mm focal length lens:

Beam diameter (short direction) is less than 200 microns.

Maximum Angle of incidence is 65°

Components

Light Source:

Model X: 150W Xenon lamp

Model D: Combined Deuterium/Quartz-Tungsten Halogen lamps

Compensators:

Patented achromatic design

Detector:

To 1000nm: 1024 pixel silicon CCD 1000-1690nm: 256 pixel InGaAs Array

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Measurement Quantities

Spectroscopic Ellipsometry:

 Ψ (0-90°) and Δ (0-360°)

N,C, and S

Intensity:

%Transmission and %Reflection

Depolarization: %Depolarization

Generalized Ellipsometry*:

AnE, Asp, and Aps (3 ratios of generalized Jones matrix)

Mueller Matrix*:

All 15 normalized elements of the Mueller-matrix (normalized to m11).

*Useful for measuring and characterizing anisotropic materials with cross-polarization.

Straight-Through Accuracy

(10 second measurement of empty-beam, met by 95% of all wavelengths)

Psi: $45^{\circ} \pm 0.02^{\circ}$ Delta: $0^{\circ} \pm 0.05^{\circ}$

Depolarization: $0\% \pm 0.5\%$

15 normalized Mueller-Matrix elements:

Diagonal: 1 ± 0.002 Off-Diagonal: 0 ± 0.002

Off-Sample Data Fit Accuracy

(10 second measurement of nominally 25nm SiO2/Si)

MSE defined in terms of N,C,S < 0.002

MSE defined in terms of Mueller-matrix elements < 0.002

Thickness Precision:

(30 consecutive (static) 10-second measurements of nominally 25nm SiO2/Si)

Standard deviation in thickness < 0.005 nm